



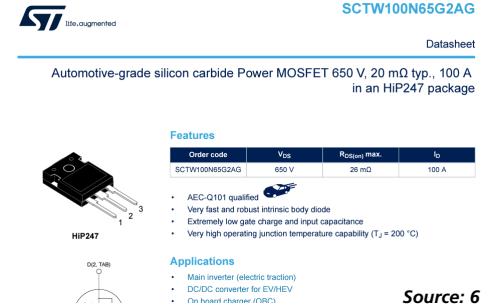
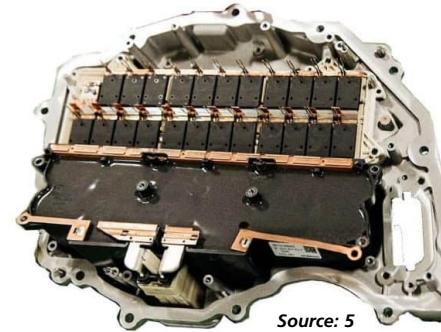
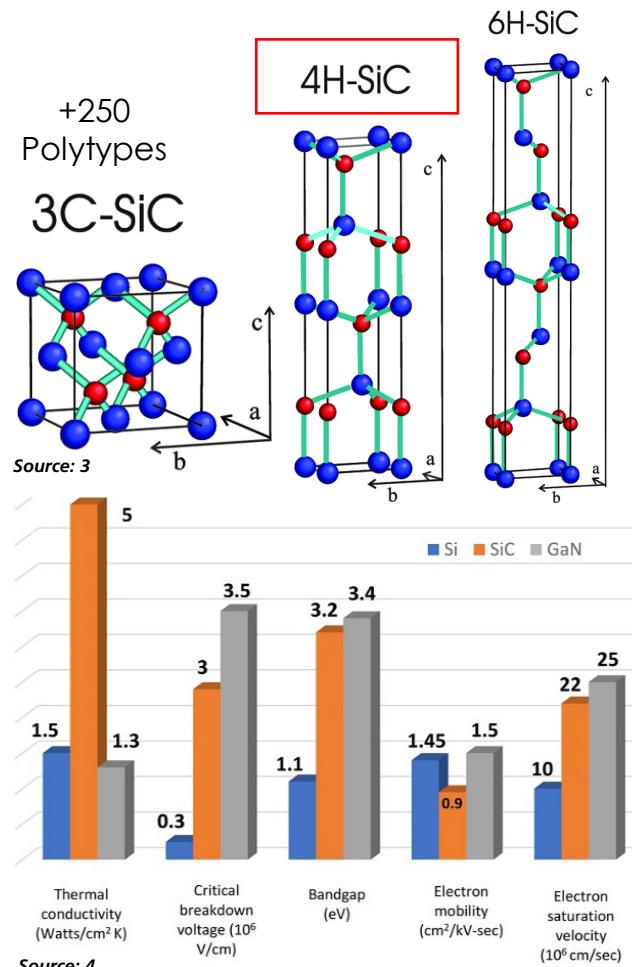
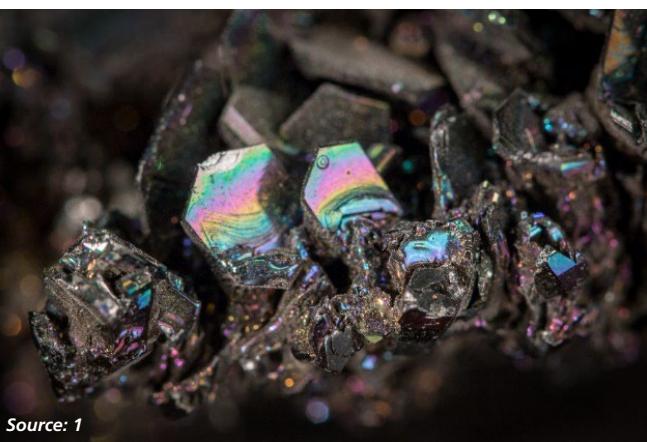
Milliseconds Power Cycling (PC_{msec}) driving bipolar degradation in Silicon Carbide Power Devices

- Sibasish Laha, *Scientist at Fraunhofer IISB*
- Dr. Davood Momeni, *SiC Product Quality Engineer at Nexperia Germany*
- Dr. Jürgen Leib, *Group Manager at Fraunhofer IISB*
- Andreas Schletz, *Founder of Schletz GmbH*
- Prof. Dr.-Ing. Martin März, *Director of Fraunhofer IISB*
- Christian Liguda, *Sr. Principal Product Quality Engineer at Nexperia Germany*
- Dr. Firas Faisal, *Sr. SiC Material Defects Engineer at Nexperia Germany*

In collaboration with

Silicon Carbide (SiC)?

From meteorites to power electronics



Tesla Model 3 Inverter with STMicroelectronics
650V/100A SiC MOSFET



Tesla Model 3 - 2018

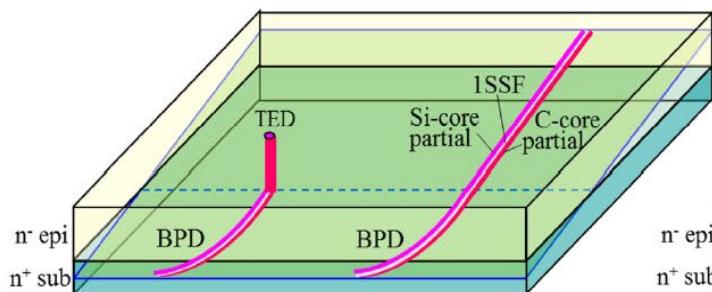
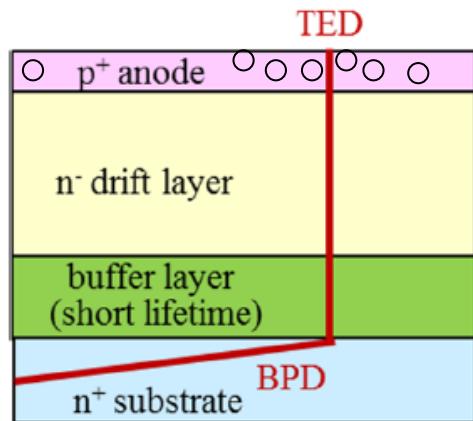
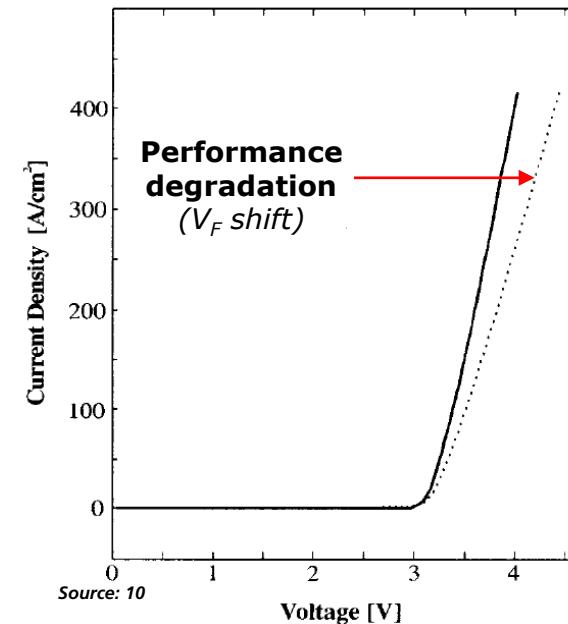
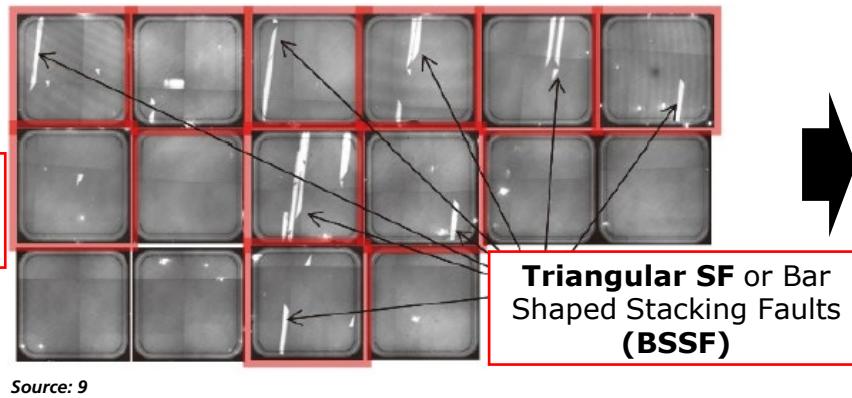
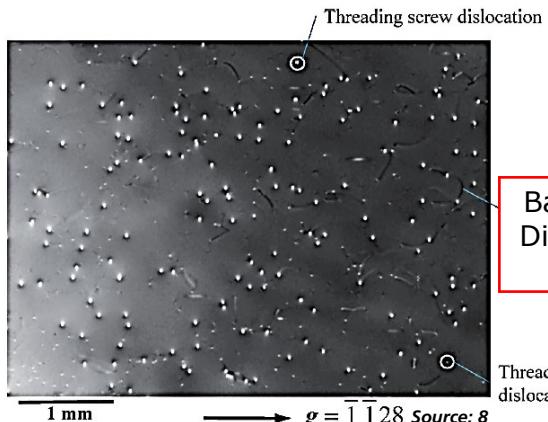
Higher **blocking** voltages (>650 V) – Better **thermal** performance – Occupy **less space** compared to Si

The challenges!

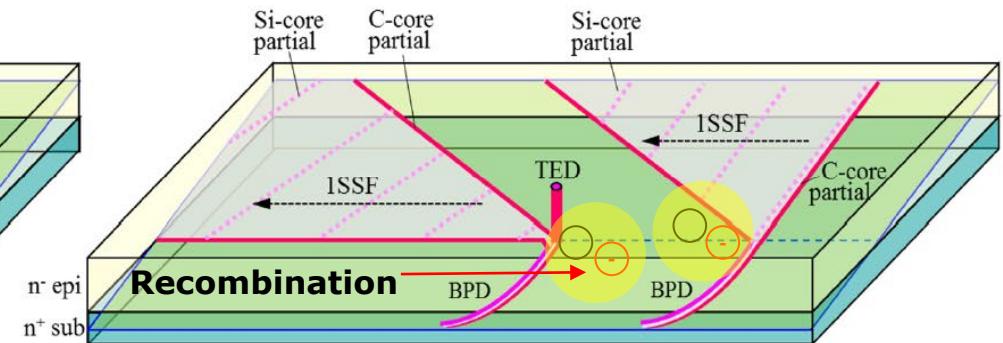
Bipolar Degradation (BD) in SiC PN devices

Background

Recombination induced stacking faults causing BD during operation



Propagation during processing



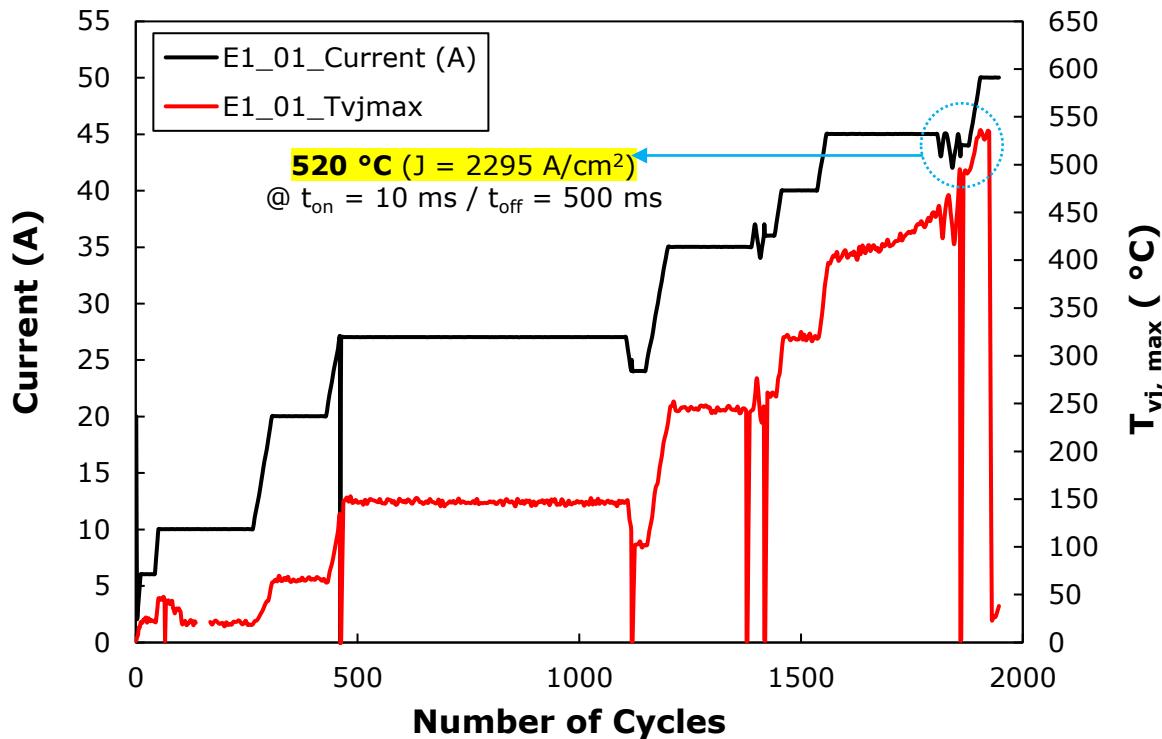
Expansion during device operation (depends on current density)

How to test Bipolar degradation in real world?

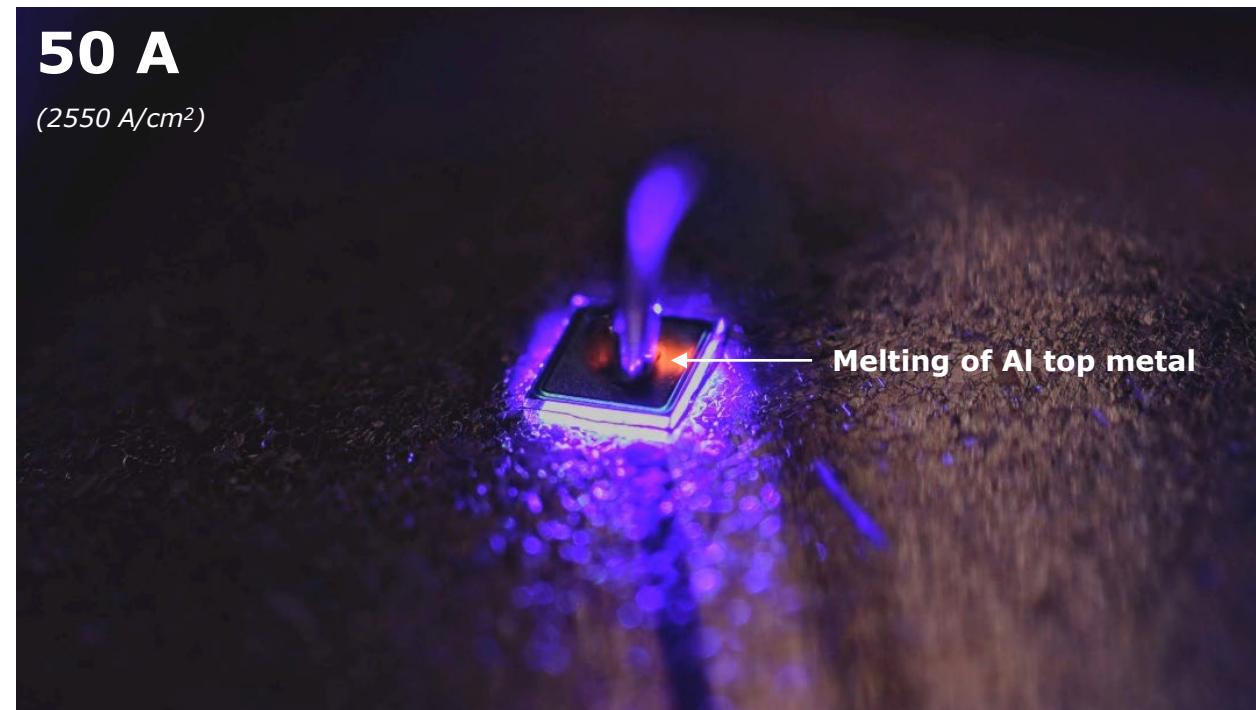
High current short pulse (10 ms)

Implementing high current density with controlled heating – as per literatures

Pulsed current for high current density and lower T_{vj}



Device temperature is close to Al melting temperature (660 °C)



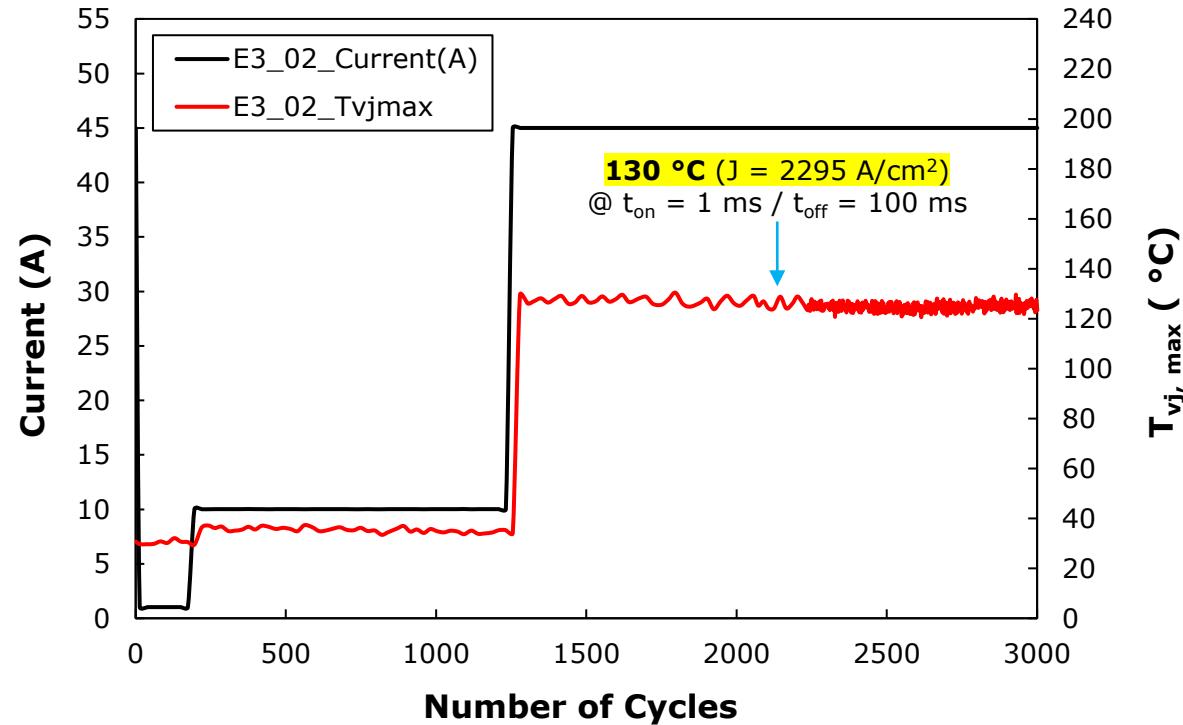
Device destruction in time

The solution?

Power Cycling millisecond (PC_{msec} of 1 ms)

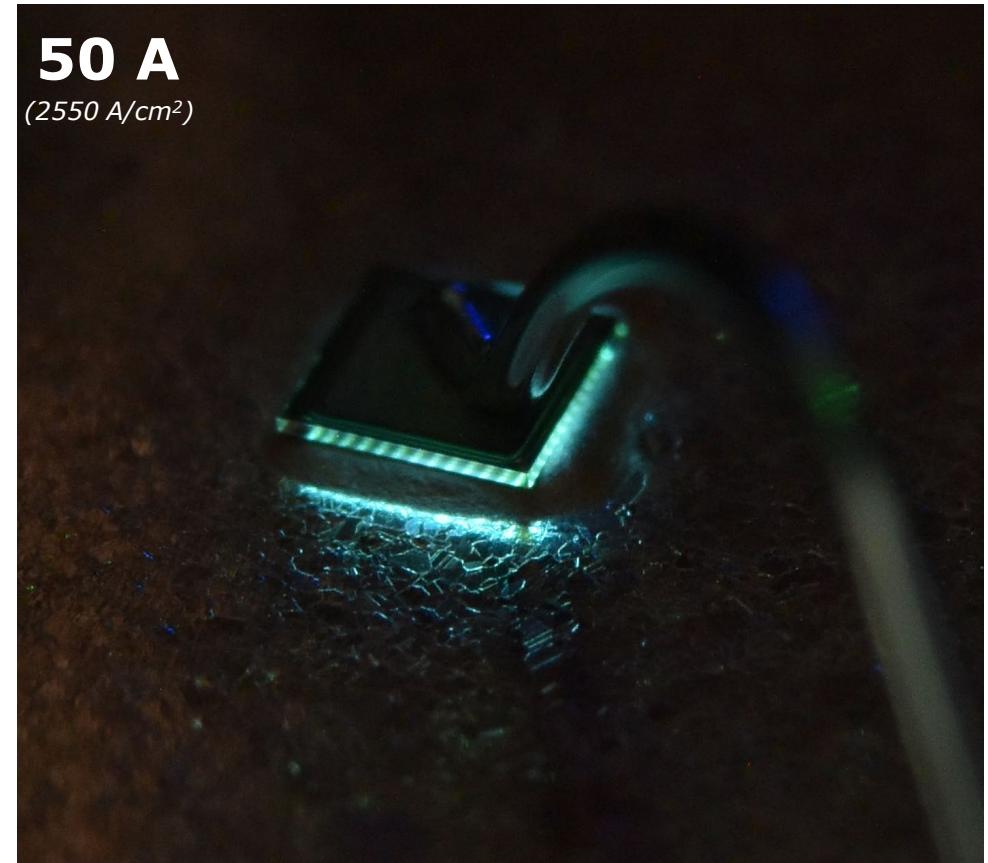
Replicating surge conditions while controlling device temperatures

High current density and control on T_{vj, max}



T_{vj, max} is below maximum device temperature (175°C)

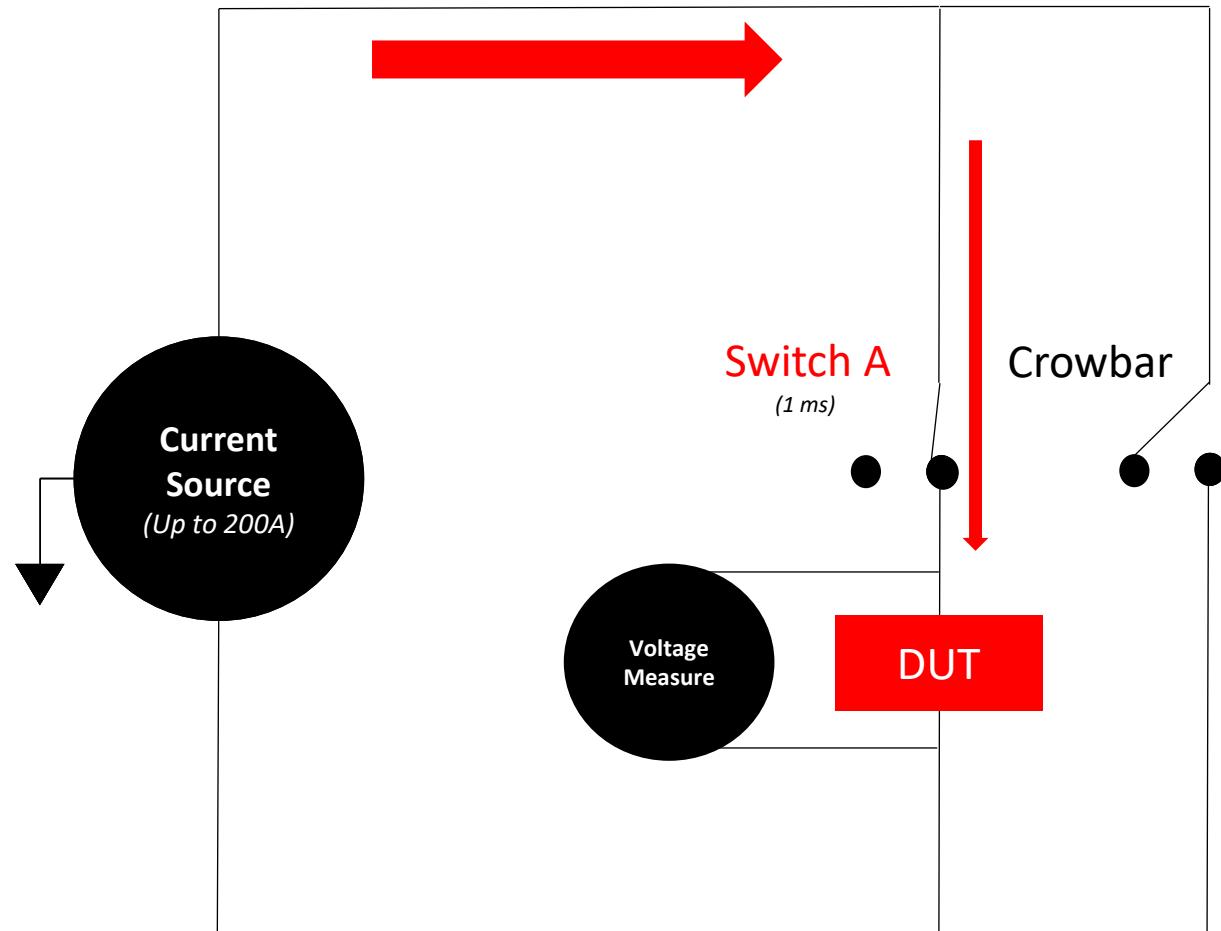
T_{vj, max} is below chip solder melting point (240°C)



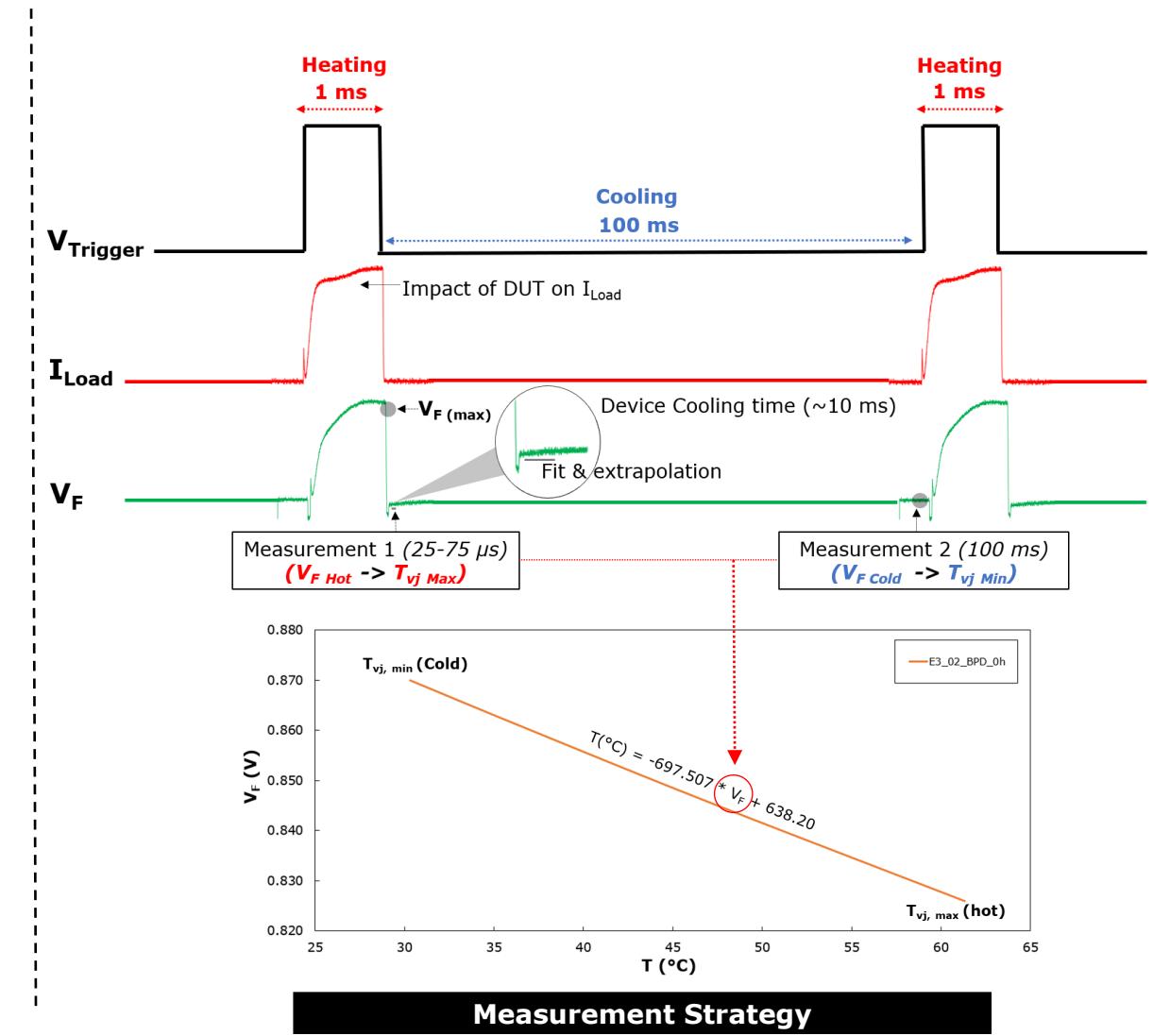
How to do this test?

Test Concept – Bipolar Degradation

Optimizing power cycling setup for short pulses



Test Schematic



Measurement Strategy

Device Technology Background

Conceptual description of the experimental DUTs

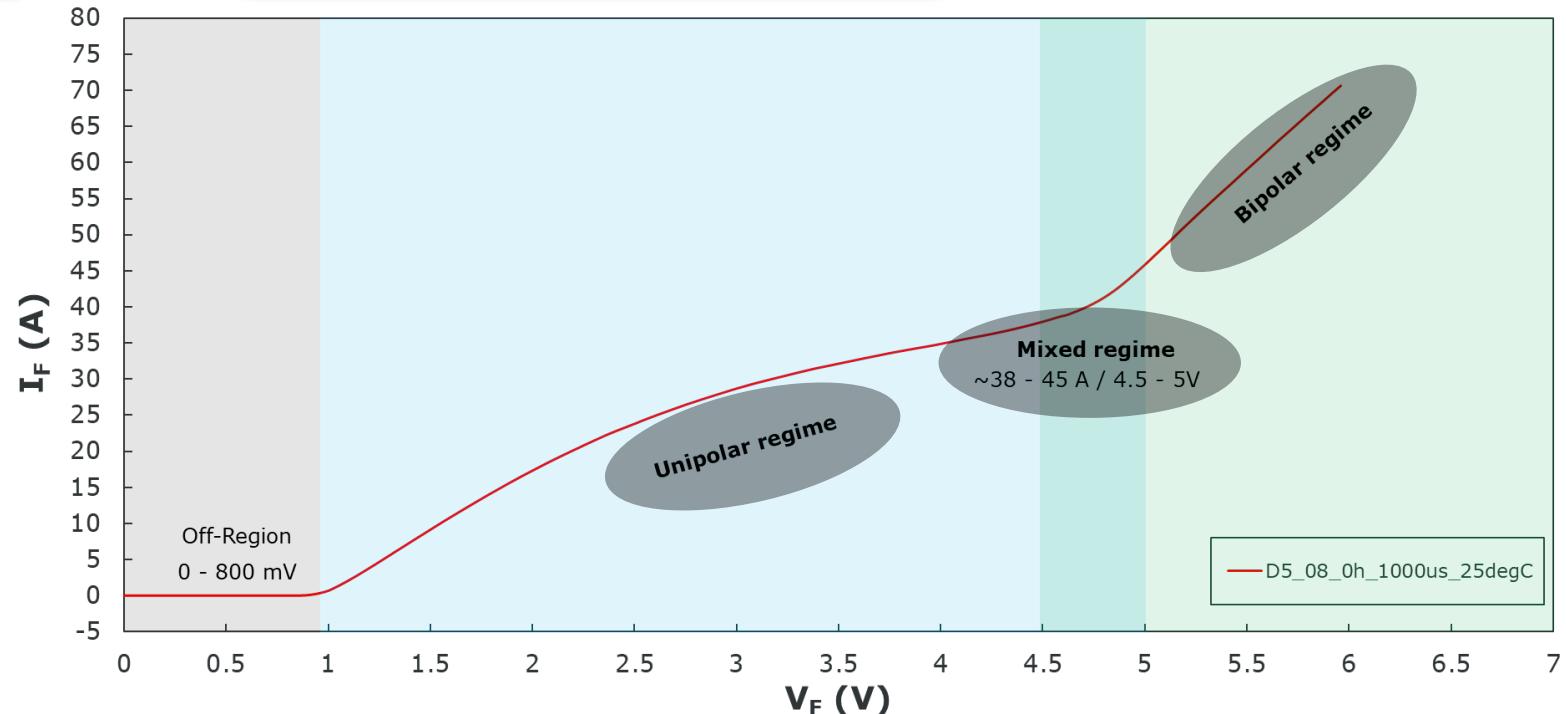
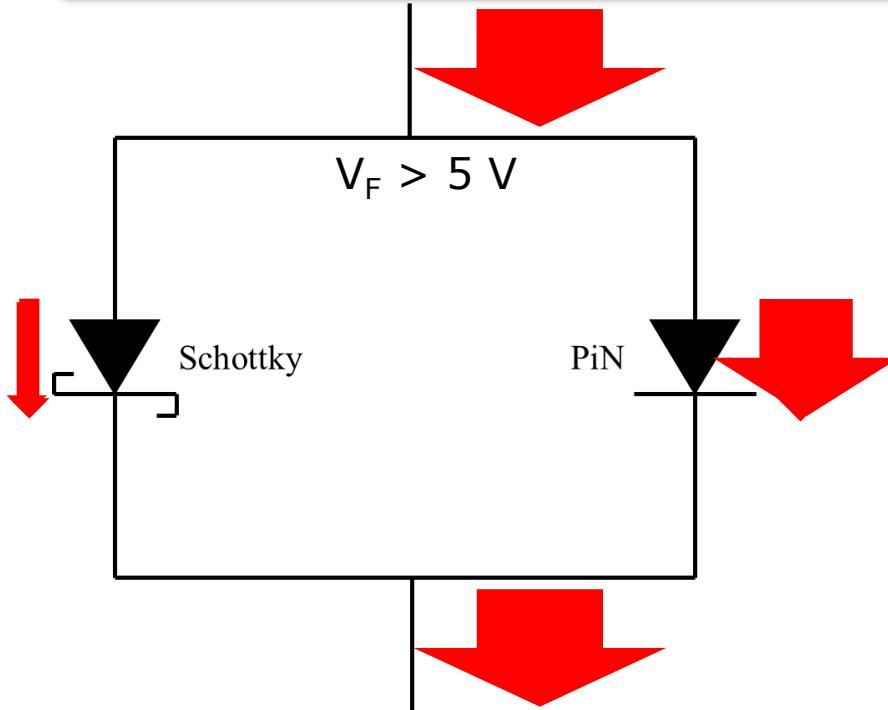
4H-SiC - Wide bandgap (Higher V_{BR})

Schottky - Low V_{th}

PiN - **Surge** current capability

Merged PiN Schottky (MPS)

(650 V / 10 A)



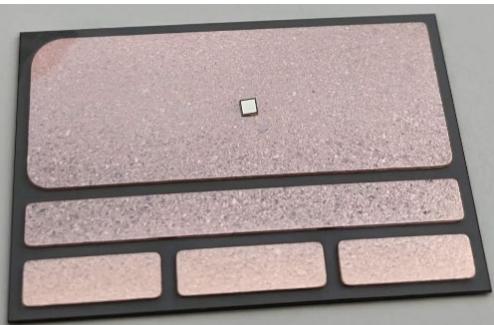
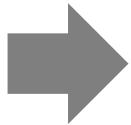
Things needed for experiment?

Sample Preparation - 1

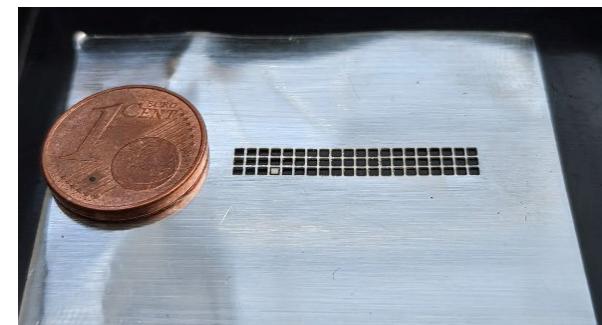
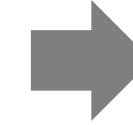
Assembly of DUTs for test



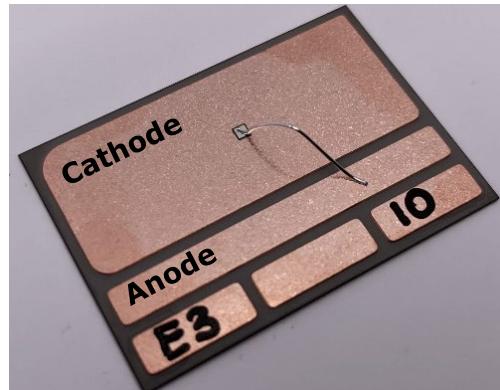
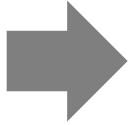
Bare die SiC MPS diode
($1.4 \text{ mm} \times 1.4 \text{ mm}$)



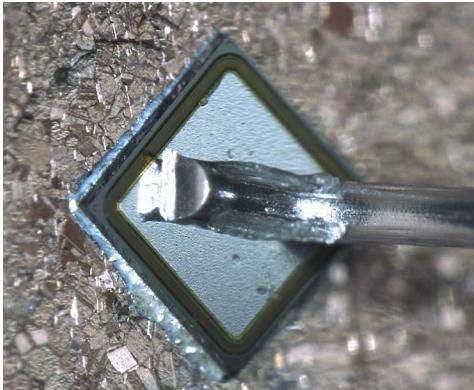
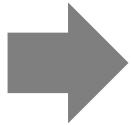
Chip placement on Si_3N_4 AMB substrate



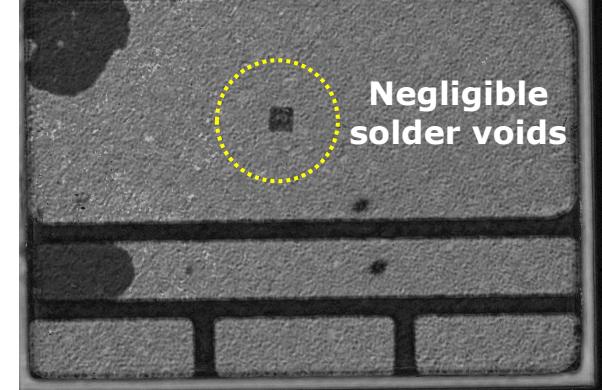
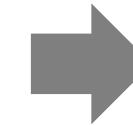
Laser cutting of Sn-Ag preforms
($800 \mu\text{m} \times 800 \mu\text{m}$)



Soldering and bonding for electrical connection



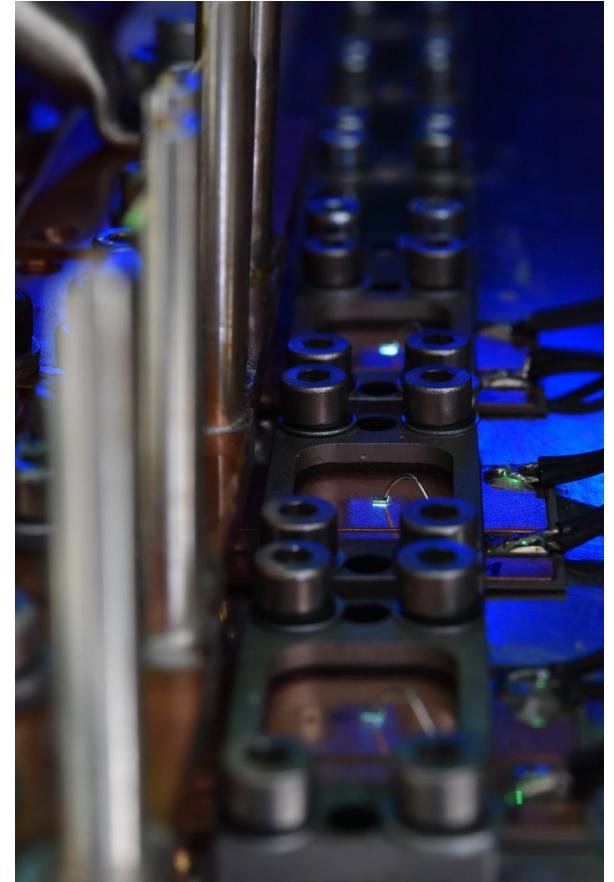
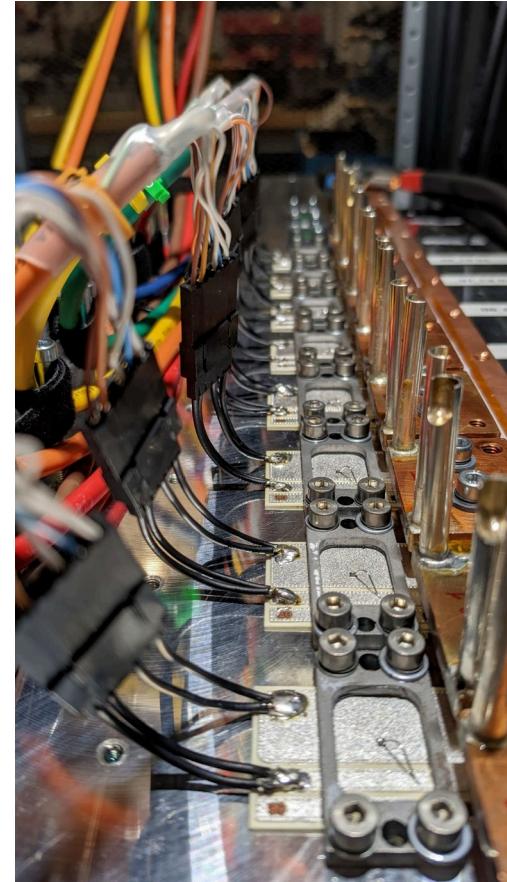
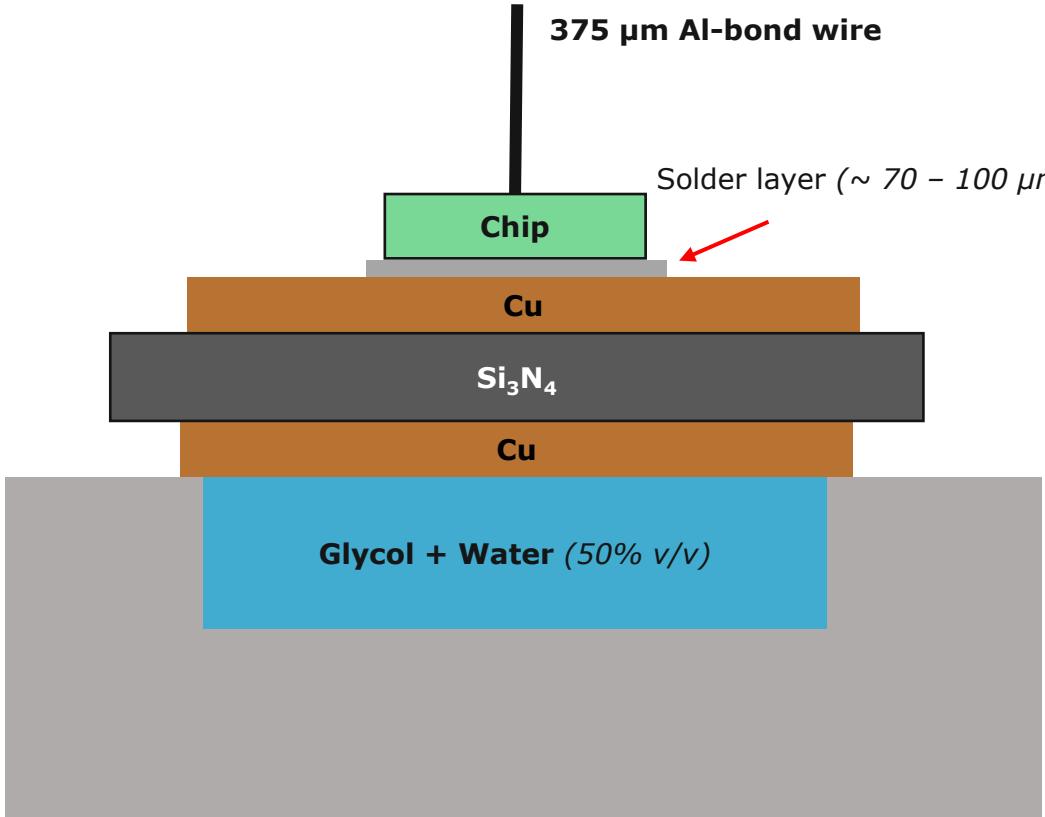
Visual inspection



Inspection under Acoustic microscopy

DUT mounting

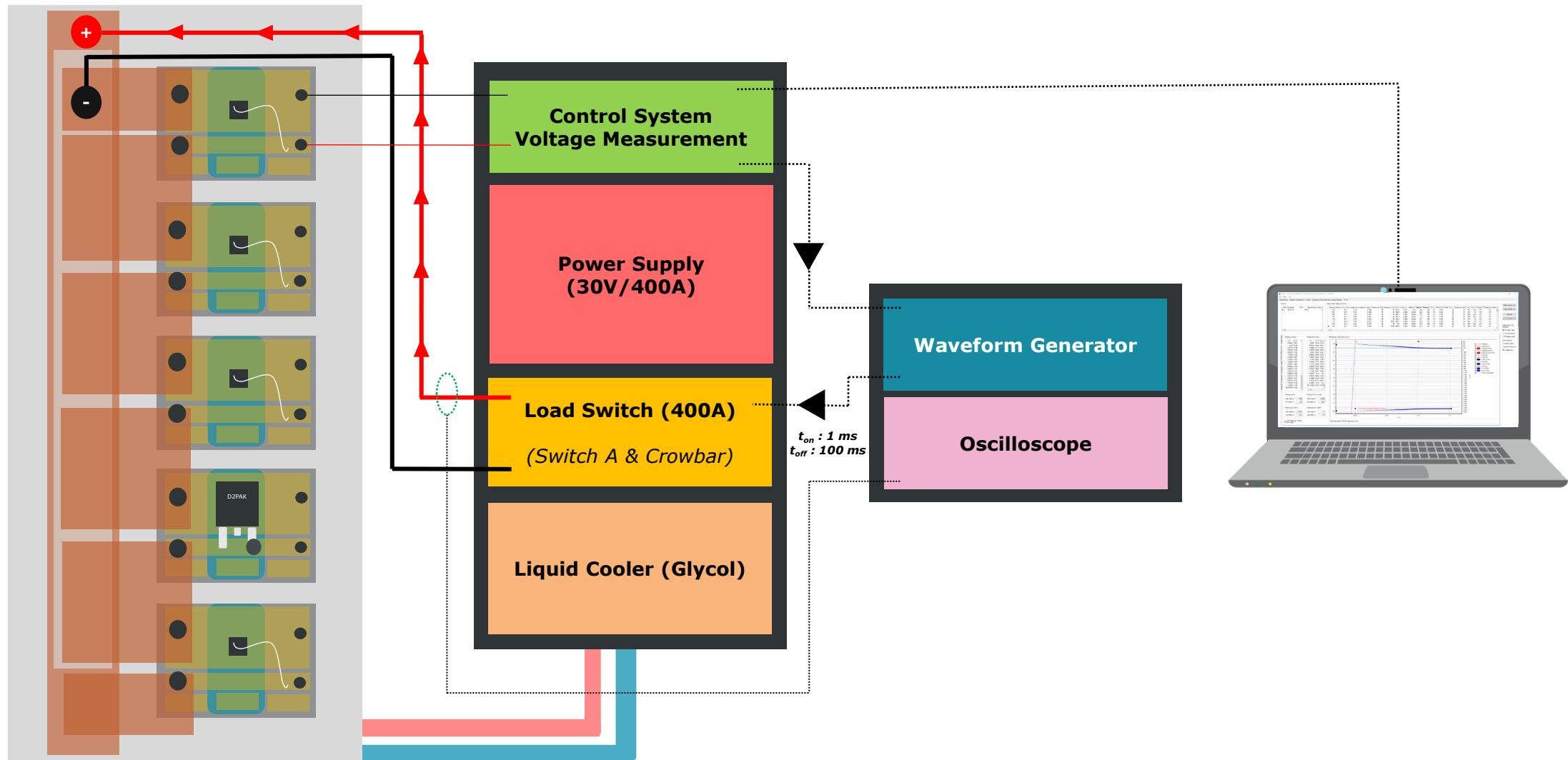
Assembly of bare dies in testbench



Bare dies mounted on testbench

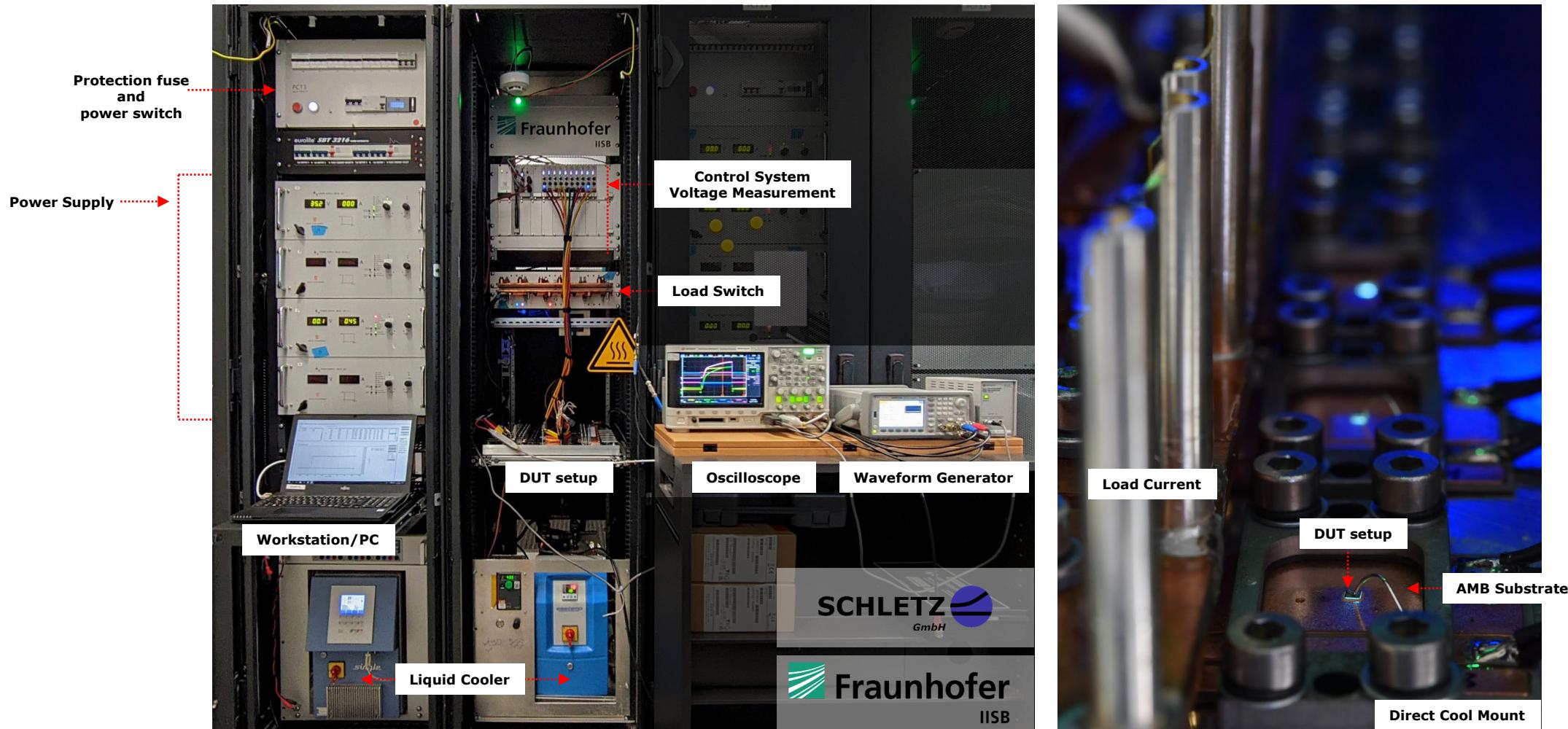
Experimental Setup – 1 (Schematic)

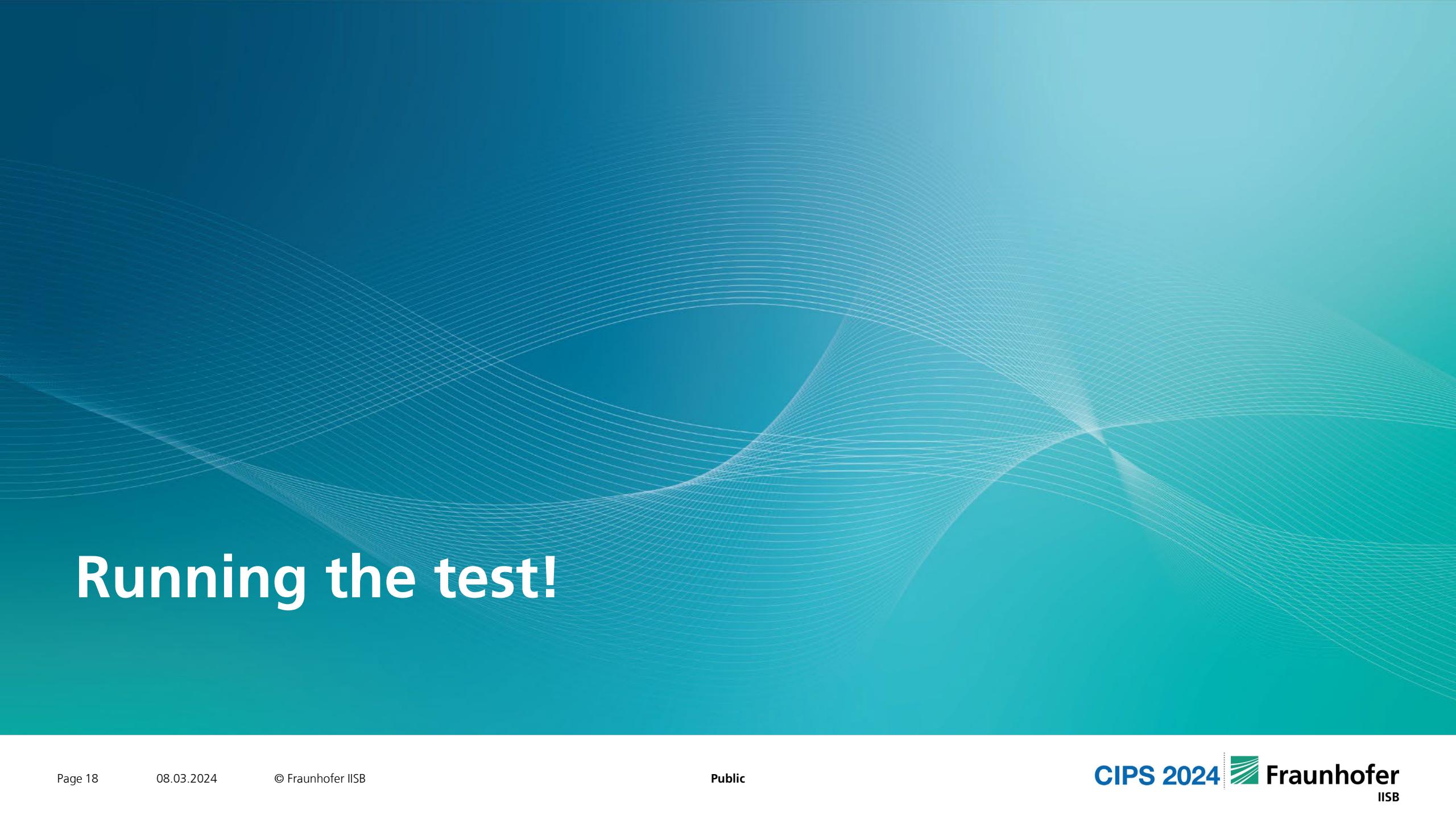
Setup overview



Experimental Setup – 2 (Implementation)

Description of the actual testbench





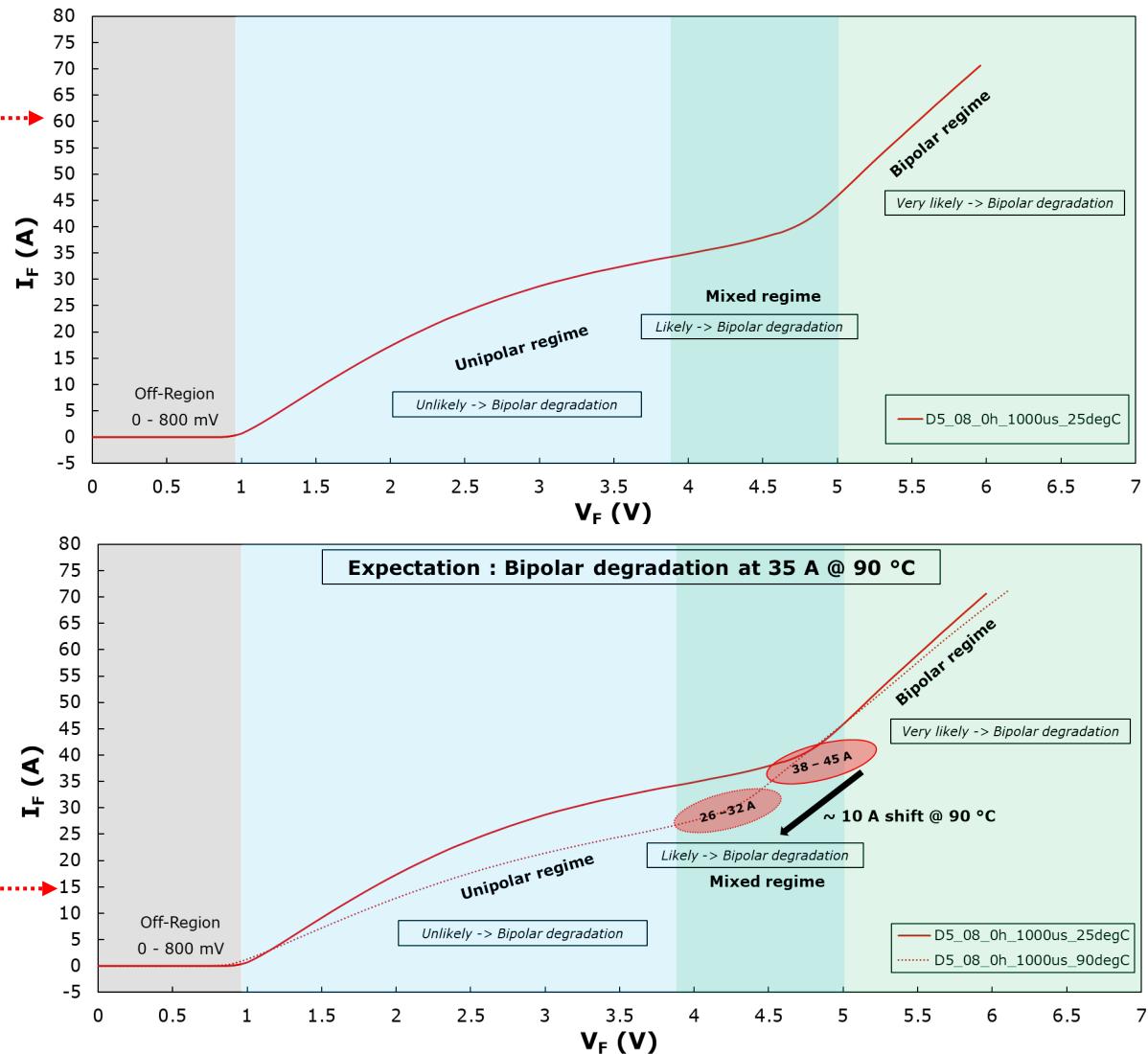
Running the test!

Test Strategy

Variation of current, temperature and die types

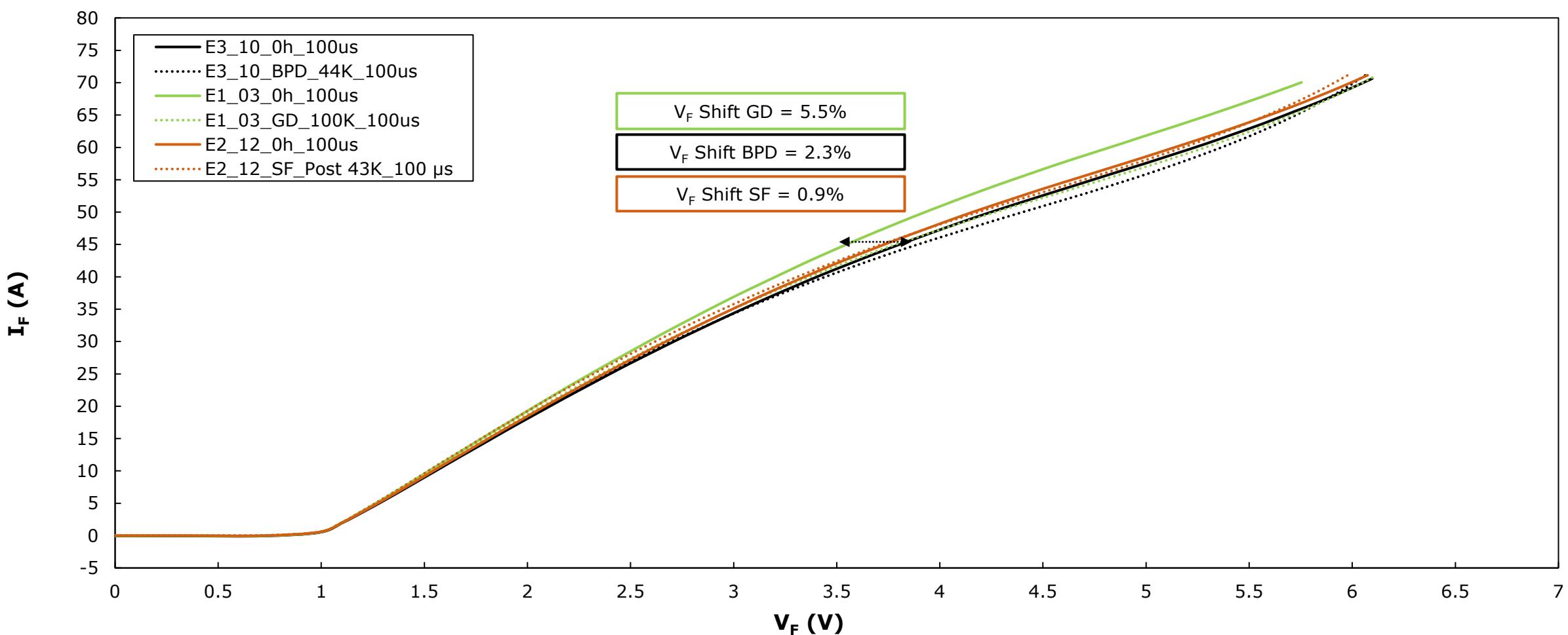
Pulsed heating current (1 ms)	$T_a = 25^\circ\text{C}$	$T_a = 85^\circ\text{C}$
35 A (1785 A/cm^2) (Unipolar Regime)	✓ ✓ ✓ GD/BPD/SF	✓ ✓ GD/BPD/SF
45 A (2295 A/cm^2) (Mixed Regime)	✓ ✓ ✓ GD/BPD/SF	✓ ✓ ✓ GD/BPD/SF
55 A (2806 A/cm^2) (Bipolar Regime)	✓ ✓ ✓ GD/BPD/SF	✓ ✓ ✓ GD/BPD/SF

- $T_{vj, max}$ is set to 240°C to minimize solder degradation



Pre/Post Characterization Results (45A) - 1

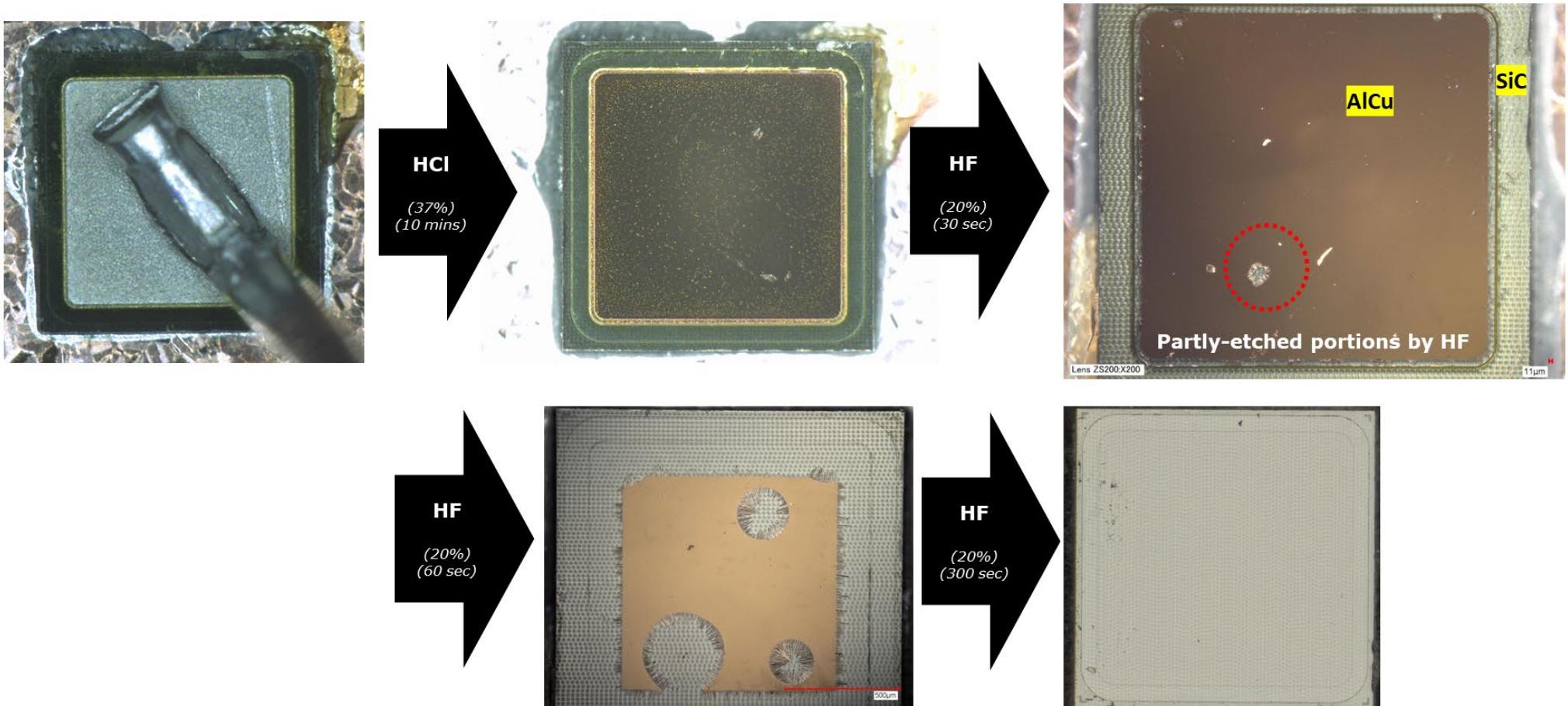
I-V Sweep measurement



- Tested at room temperature : ($T_a = 23^\circ\text{C}$), Configuration : $I_{F_{max}} = 70 \text{ A}$, $t_p = 100 \mu\text{s}$

Post-test failure analysis - 1

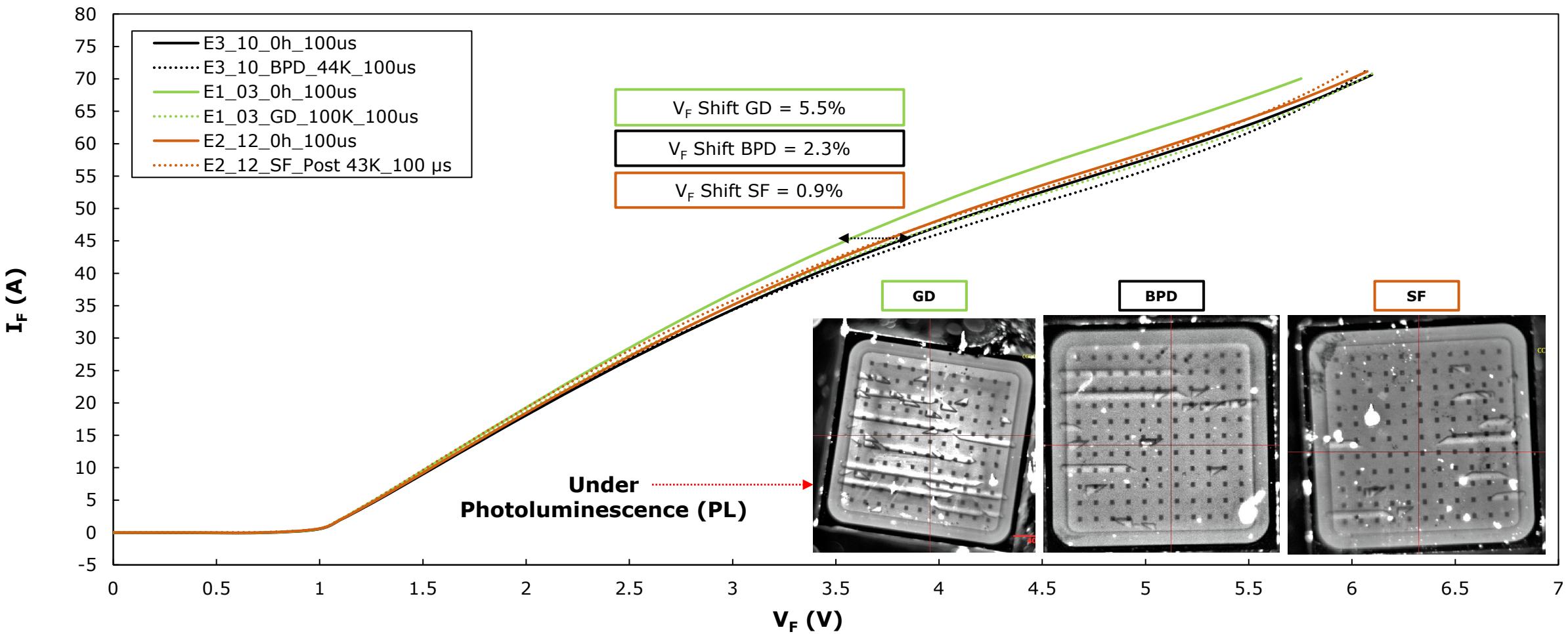
Removal of power and Schottky metal



- The DUT was measured with VHX 7000 digital microscope with 100x magnification

Pre/Post Characterization Results (45A) - 2

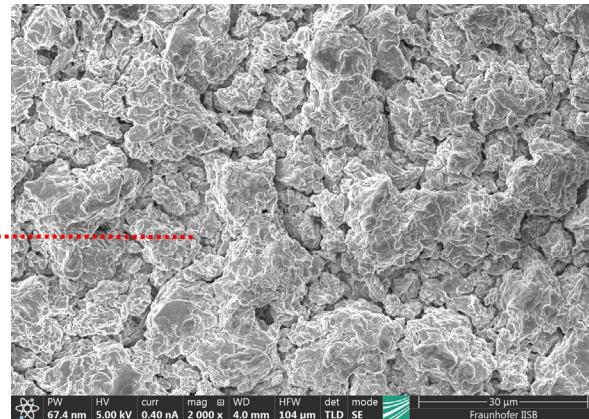
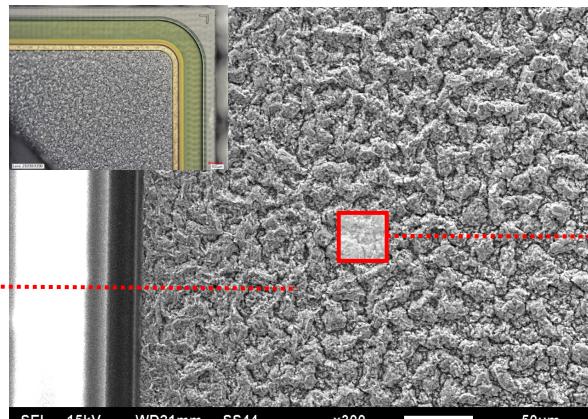
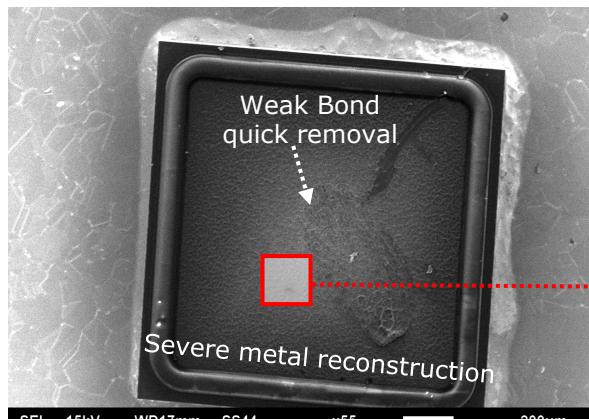
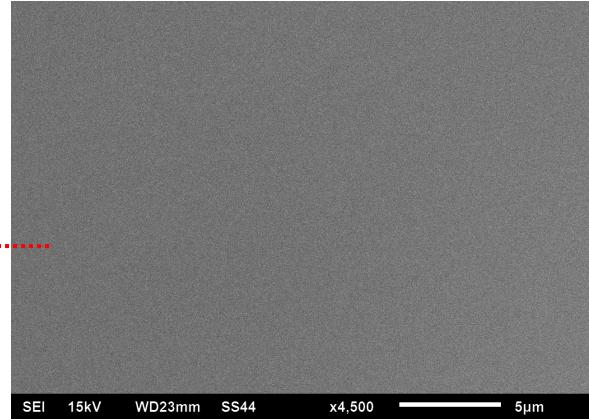
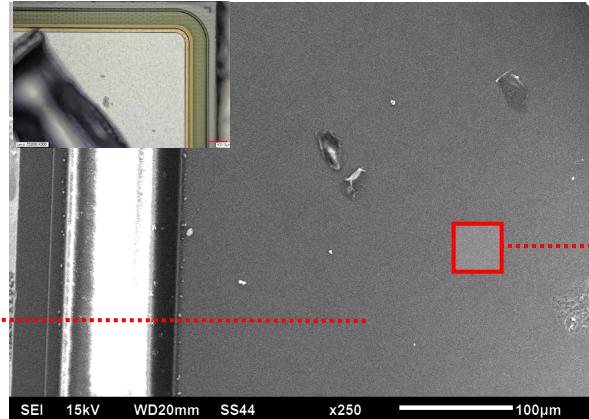
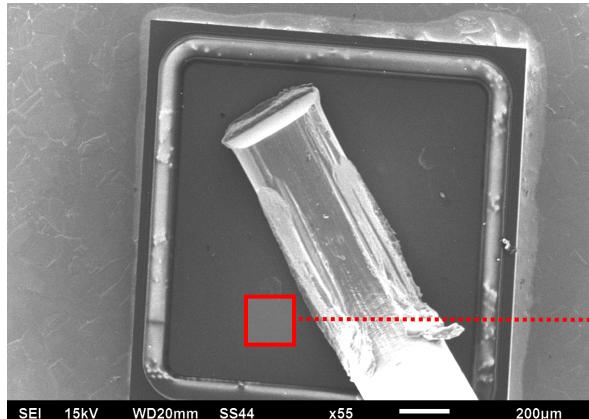
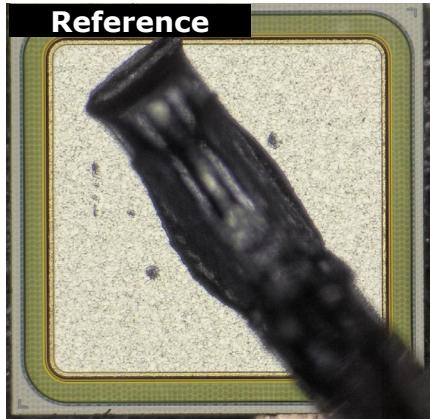
I-V Sweep measurement – Forward bias



- Tested at room temperature : ($T_a = 23^\circ\text{C}$), Configuration : $I_F_{max} = 70 \text{ A}$, $t_p = 100 \mu\text{s}$

Post-test failure analysis - 2

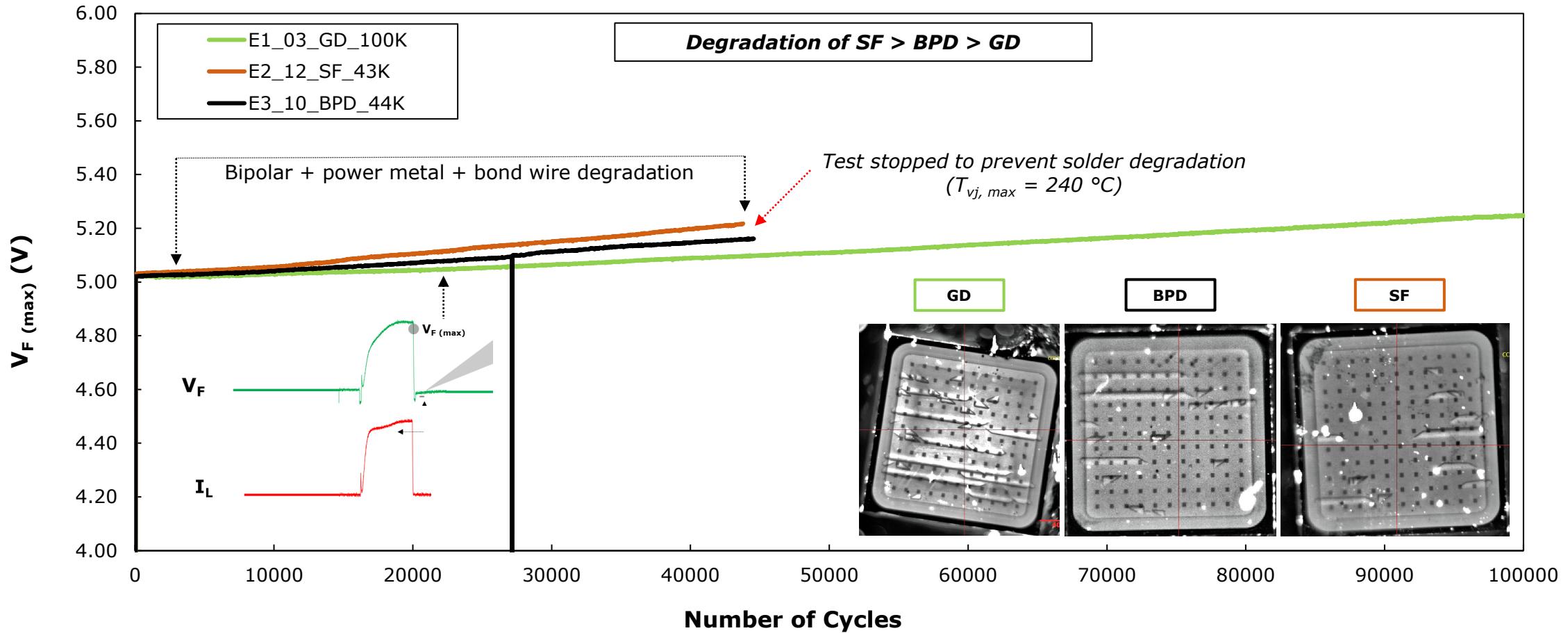
Metal Reconstruction



- The DUTs were inspected under JEOL-6610 Series Scanning Electron Microscope

Variation of V_F (max) over cycles

Heating V_F measurement during test

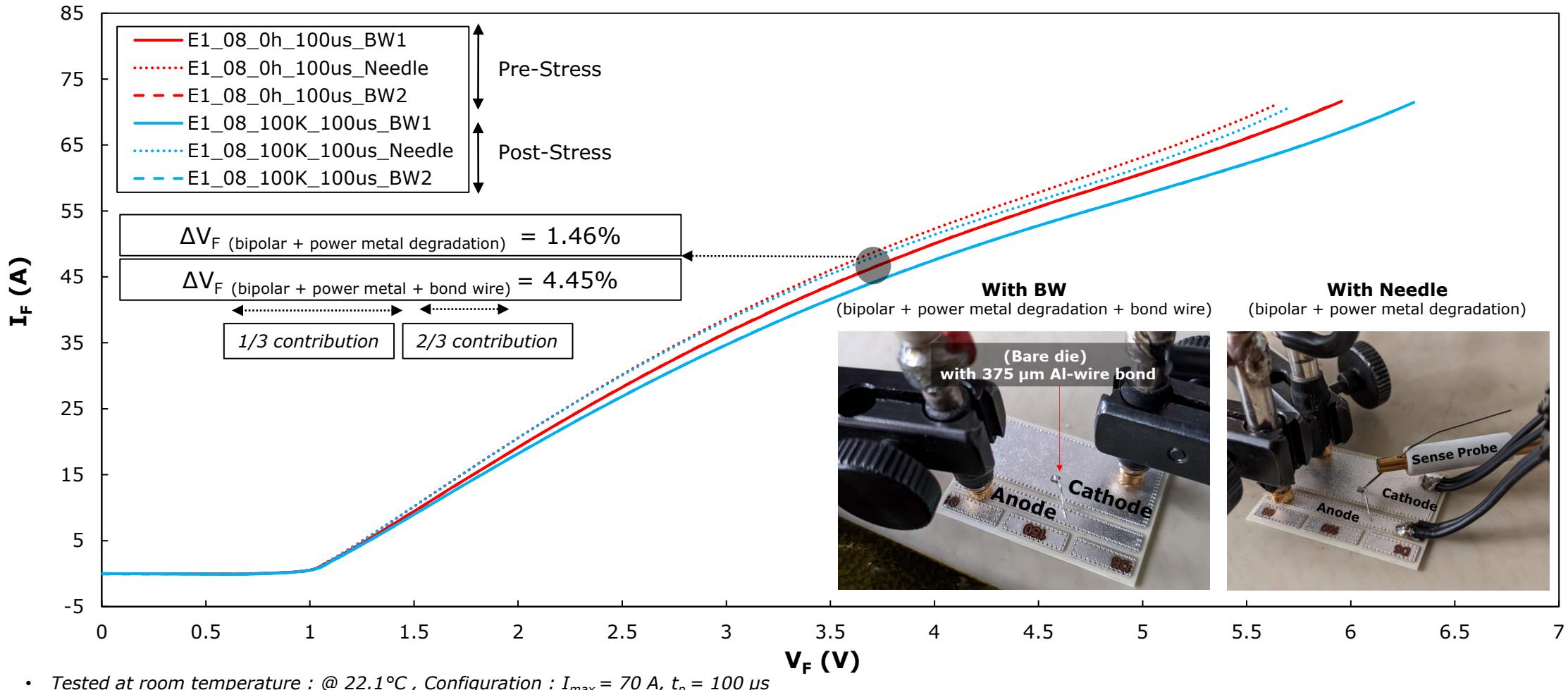


- Test Parameters : Load Current = 45 A (Coolant Temperature = 25 °C (Glycol + water), $t_{on} = 1 \text{ ms}$ and $t_{off} = 100 \text{ ms}$

How much is the Bipolar vs. Thermal degradation?

Evaluating bipolar and thermal degradation

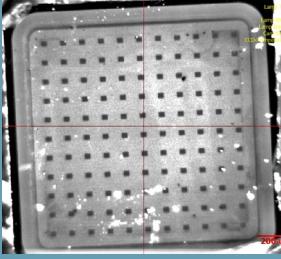
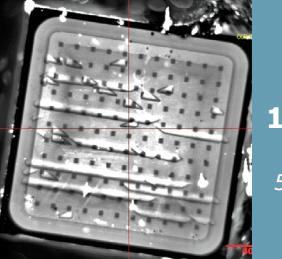
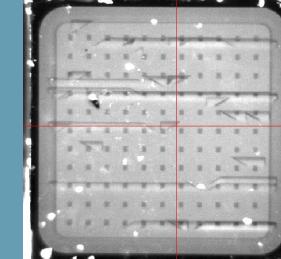
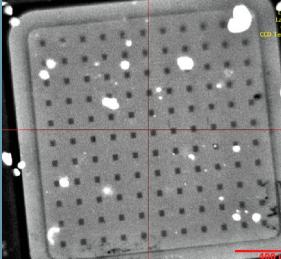
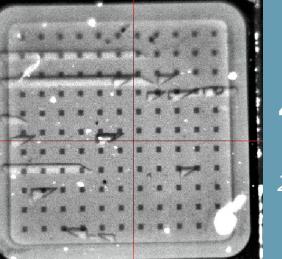
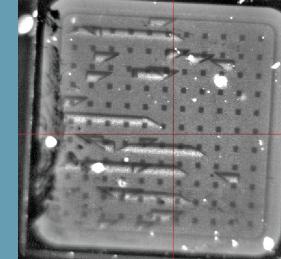
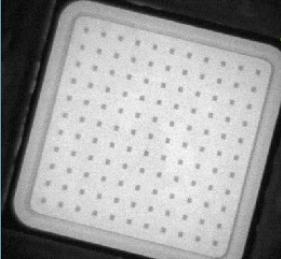
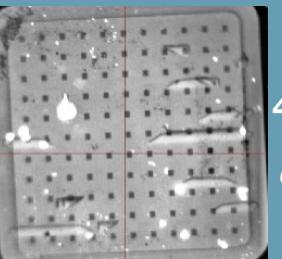
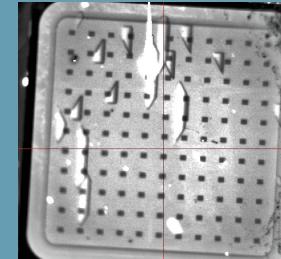
I-V Sweep with & w/o bond wire – Forward bias



Summary

Overall Results after Photoluminescence

Tested samples after metal etch and PL scan

Device Type \ Current	35A (1785 A/cm^2)	45A (2295 A/cm^2)	55A (2806 A/cm^2)
GD	E1_06  100 sec -4% shift	E1_03  100 sec 5.5% shift	E1_04  32 sec 13% shift
BPD	E3_15  100 sec 0.5% shift	E3_10  44 sec 2.3% shift	E3_11  13 sec 7.3% shift
SF	E2_14  100 sec -3% shift	E2_12  43 sec 0.9% shift	E2_11  6.5 sec 6.7% shift

Summary of results and findings

Highlights and lowlights based on test evaluation



- 3 devices were test devices out of 50

Inferences and future scope

Key pointers

Shorter $t_p \leq 1 \text{ ms}$ is essential to **minimize thermal degradation**

BD occurred at **> 3.5 times J_{nominal}** or **> 35 A**, regardless of temperature

Precise **Characterization without** relying on the **degraded bond wire interconnect**



Etching of the samples to **investigate** nucleation **source**

Measure **power metal degradation** using **four-point measurement** pre/post stress

Image References

1. <https://www.usgs.gov/media/images/silicon-carbide-0>
2. <https://www.etsy.com/nz/listing/992754356/colorful-silicon-carbide-crystal>
3. https://www.researchgate.net/publication/34444231_Lanthanide_doped_wide_band_gap_semiconductors_Elektronische_Ressource_intra-4f_luminescence_and_lattice_location_studies/figures?lo=1
4. <https://www.powersystemsdesign.com/articles/how-sic-and-gan-enable-higher-power-conversion-efficiency/138/17281>
5. <https://www.pntpower.com/tag/device/>
6. <https://www.st.com/en/power-transistors/sctw100n65g2ag.html#documentation>
7. <https://www.pntpower.com/tesla-model-3-powered-by-st-microelectronics-sic-mosfets/>
8. K. Omote, "Crystal defects in SiC wafers and a new X-ray topography system," in Proc. Conference Name, Year, pp. Page numbers. [Online]. Available: <https://api.semanticscholar.org/CorpusID:30917668>
9. H. Tsuchida, K. Murata, T. Tawara, M. Miyazato, T. Miyazawa and K. Maeda, "Suppression of Bipolar Degradation in 4H-SiC Power Devices by Carrier Lifetime Control," 2019 IEEE International Electron Devices Meeting (IEDM), San Francisco, CA, USA, 2019, pp. 20.1.1-20.1.4, doi: 10.1109/IEDM19573.2019.8993530
10. P. Bergman, H. Lendenmann, P. Nilsson, U. Lindefelt, and P. Skytt, "Crystal Defects as Source of Anomalous Forward Voltage Increase of 4H-SiC Diodes," Materials Science Forum - MATER SCI FORUM, vol. 353-356, pp. 299-302, 2001. [Online]. Available: DOI: 10.4028/www.scientific.net/MSF.353-356.299.

Knowledge References

- [1] P. Bergman, H. Lendenmann, P. Nilsson, U. Lindefelt, and P. Skytt, "Crystal Defects as Source of Anomalous Forward Voltage Increase of 4H-SiC Diodes," Materials Science Forum - MATER SCI FORUM, vol. 353-356, pp. 299-302, 2001. [Online]. Available: DOI: 10.4028/www.scientific.net/MSF.353-356.299.
- [2] S. Palanisamy, T. Basler, J. Lutz, C. Künzel, L. Wehrhahn-Kilian, and R. Elpelt, "Investigation of the bipolar degradation of SiC MOSFET body diodes and the influence of current density," in 2021 IEEE International Reliability Physics Symposium (IRPS), Monterey, CA, USA, 2021, pp. 1-6. [Online]. Available: DOI: 10.1109/IRPS46558.2021.9405183.10.1109/IRPS46558.2021.9405183.
- [3] J. Lutz, H. Schlangenotto, U. Scheuermann, and R. De Doncker, "Semiconductor Power Devices," 2018. [Online]. Available: DOI: 10.1007/978-3-319-70917-8, pp. 280.
- [4] U. Scheuermann and R. Schmidt, "Impact of solder fatigue on module lifetime in power cycling tests," in Proceedings of the 2011 14th European Conference on Power Electronics and Applications, Birmingham, UK, 2011, pp. 1-10.
- [5] Y. Ebihara et al., "Suppression of Bipolar Degradation in Deep-P Encapsulated 4H-SiC Trench MOSFETs up to Ultra-High Current Density," in 2019 31st International Symposium on Power Semiconductor Devices and ICs (ISPSD), 2019, pp. 35-38.
- [6] K. Omote, "Crystal defects in SiC wafers and a new X-ray topography system," in Proc. Conference Name, Year, pp. Page numbers. [Online]. Available: <https://api.semanticscholar.org/CorpusID:30917668>
- [7] S. Palanisamy, J. Kowalsky, J. Lutz, T. Basler, R. Rupp, and J. Moazzami-Fallah, "Repetitive surge current test of SiC MPS diode with load in bipolar regime," in 2018 IEEE 30th International Symposium



Thank You for your attention

Contact

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